Publications


Low-Voltage electron-optical system for the high speed inspection of integrated circuits

Dynamic performance of a scanning x-y stage for automated electron-beam inspection

Conceptual models for understanding and minimizing coulomb interactions

An electron-beam inspection system for x-ray mask production

Requirements and performance of an electron-beam column designed for x-ray mask inspection

Electrostatic lens of very low spherical aberration

U. S. Patents Granted

Method of Operation for SLM-Based Optical Lithography Tool
7,719,753 (2010)

Apparatus for SLM-Based Optical Lithography with Gray Level Capability
7,639,416 (2009)

Gray Level Method for SLM-Based Optical Lithography
7,508,570 (2009)

Continuous Direct-Write Optical Lithography

Lithography System and Method for Device Manufacture
6,753,947 (2004)

Motion Compensation System and Method for Lithography
6,556,279 (2003)

Inspecting optical masks with electron beam microscopy
5,717,204 (1998) and 5,665,968 (1997)

Electron beam inspection system and method

Method for opens/shorts testing of capacitively coupled networks in substrates using electron beams
5,057,773 (1991)

Apparatus and method for opens/shorts testing of capacitively coupled networks in substrates using electron beams
4,943,769 (1990)

Electron lens
4,330,708 (1982)
Korea Patents Granted

*Continuous Direct-Write Optical Lithography*

Japan Patents Granted

*Continuous Direct-Write Optical Lithography*

China Patents Granted

*Continuous Direct-Write Optical Lithography*
ZL03824263.X (2009)

Taiwan Patents Granted

*Continuous Direct-Write Optical Lithography*
I 266961 (2006)

Europe Patents Granted
